

METHOD FOR THIN FILM LASER REFLECTANCE CORRELATION FOR SUBSTRATE ETCH ENDPOINT

ABSTRACT

A method of etching a substrate, includes measuring a reflectance signal from a
5 reflective material deposited on the substrate as the substrate is being etched, correlating the
substrate etch rate to the reflectance signal from the reflective material, and using the etch
relation between the substrate and the reflective material to determine the etch target.

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